

L Number	Hits	Search Text	DB	Time stamp
8	47	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching))) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching))) and @py<=1999	USPAT	2003/10/09 16:07
9	91	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching))) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))	USPAT	2003/10/09 16:08
10	2670	(photo\$1resist or resist) same pitch	USPAT	2003/10/09 16:09
11	588	((photo\$1resist or resist) same pitch) and ((selectivity or selective or selectively) same (photo\$1resist or resist))	USPAT	2003/10/09 16:10
12	902	(photo\$1resist or resist) same pitch	EPO; JPO; DERWENT; IBM_TDB	2003/10/09 16:09
13	63	((photo\$1resist or resist) same pitch) and (selectivity or selective or selectively)	EPO; JPO; DERWENT; IBM_TDB	2003/10/09 16:10
14	1040	((photo\$1resist or resist) same pitch) and (trim or trimming or trimmed or trimed or narrow or narrower or narrowed)	USPAT	2003/10/09 16:11
15	306	((photo\$1resist or resist) same pitch) and ((selectivity or selective or selectively) same (photo\$1resist or resist))) and (trim or trimming or trimmed or trimed or narrow or narrower or narrowed)	USPAT	2003/10/09 16:11
16	301	(((((photo\$1resist or resist) same pitch) and ((selectivity or selective or selectively) same (photo\$1resist or resist))) and (trim or trimming or trimmed or trimed or narrow or narrower or narrowed)) and @ay<=2001	USPAT	2003/10/09 16:12
17	282	(((((photo\$1resist or resist) same pitch) and ((selectivity or selective or selectively) same (photo\$1resist or resist))) and (trim or trimming or trimmed or trimed or narrow or narrower or narrowed)) and @ay<=2001) and (etch or etching)	USPAT	2003/10/09 16:12
18	169	(((((photo\$1resist or resist) same pitch) and ((selectivity or selective or selectively) same (photo\$1resist or resist))) and (trim or trimming or trimmed or trimed or narrow or narrower or narrowed)) and @ay<=2001) and (etch or etching)) and (anisotropic\$3 or plasma)	USPAT	2003/10/09 16:12
-	2583	(photo\$1resist or resist) same pitch	USPAT	2003/10/09 16:08
-	28	((photo\$1resist or resist) same pitch) and (feature adj width)	USPAT	2003/06/24 11:02
-	1679	((photo\$1resist or resist) same pitch) and width	USPAT	2003/06/24 11:07
-	1084	((photo\$1resist or resist) same pitch) and width) and (etch or etching)	USPAT	2003/06/24 11:07
-	137	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching))) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))	USPAT	2003/10/09 16:10
-	88	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching))) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching))	USPAT	2003/06/24 13:46

-	47	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching))) and @py<=1999	USPAT	2003/10/09 16:07
-	26	(((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching))) and @py<=1999) not (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist)))	USPAT	2003/06/24 13:47
-	559	((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO?sub.2) and (nitride or SiN or "Si.sub.3 N.sub.4")	USPAT	2003/06/24 16:02
-	485	((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO?sub.2) and (nitride or SiN or "Si.sub.3 N.sub.4")) not (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))	USPAT	2003/06/24 14:00
-	437	(((((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO?sub.2) and (nitride or SiN or "Si.sub.3 N.sub.4")) not (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))) and (etch or etching)	USPAT	2003/06/24 13:57
-	447	((photo\$1resist or resist) same pitch) and ((oxide or SiO or SiO?sub.2) same (nitride or SiN or "Si.sub.3 N.sub.4"))	USPAT	2003/06/24 13:59
-	383	((photo\$1resist or resist) same pitch) and ((oxide or SiO or SiO?sub.2) same (nitride or SiN or "Si.sub.3 N.sub.4"))) not (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or (((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))	USPAT	2003/06/24 14:00

-	296	(((((photo\$1resist or resist) same pitch) and ((oxide or SiO or SiO?sub.2) same (nitride or SiN or "Si.sub.3 N.sub.4")))) not ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))))) and (mask or hard\$1mask)	USPAT	2003/06/24 14:02
-	168	(((((photo\$1resist or resist) same pitch) and ((oxide or SiO or SiO?sub.2) same (nitride or SiN or "Si.sub.3 N.sub.4")))) not ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))))) and (mask or hard\$1mask)) and plasma	USPAT	2003/06/24 14:03
-	167	(((((photo\$1resist or resist) same pitch) and ((oxide or SiO or SiO?sub.2) same (nitride or SiN or "Si.sub.3 N.sub.4")))) not ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))))) and (mask or hard\$1mask)) and plasma) and @ad<20011221	USPAT	2003/06/24 14:03
-	271	((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO?sub.2) and (nitride or SiN or "Si.sub.3 N.sub.4")) and pressure	USPAT	2003/06/24 16:02
-	238	(((((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO?sub.2) and (nitride or SiN or "Si.sub.3 N.sub.4")) not ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or ((((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))))) and pressure	USPAT	2003/06/24 16:03

-	200	((((photo\$1resist or resist) same pitch) and (oxide or SiO or SiO ₂) and (nitride or SiN or "Si ₃ N ₄ ")) not (((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (photo\$1resist or resist))) or ((((photo\$1resist or resist) same pitch) and width) and (etch or etching)) and ((trim or trimming or trimmed or trimed or narrow or narrower or narrowed) with (etch or etching)))) and pressure) and @py<=2001	USPAT	2003/06/24 16:04
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